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PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10026973	12/27/2001	430	5	1756	Rosasco

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\*\*CONTINUING DATA VERIFIED:

*No record*

\*\* FOREIGN APPLICATIONS VERIFIED:

JAPAN 2000-401154 12/28/2000 *AR*

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials		<input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO T&A-109
TITLE : Photomask, the manufacturing method, a patterning method, and a semiconductor device manufacturing method			
U.S. DEPT. OF COMM./PAT. & TM-PTO-436L (Rev. 12-94)			

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
		<input type="checkbox"/>	<input type="checkbox"/>
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drawn	Page Drawn
TERMINAL		Primary Examiner	
DISCLAIMER		PREPARED FOR ISSUE	
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